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APPLICANT

Philip A. Fisher et al.

FILING DATE

GROUP ART UNIT

(Use several sheets if necessary)

12/14/2001

To be determined

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE
OC	A1	09/819,342		Shields et al.			03/28/01
OC	A2	09/819,343		Gabriel et al.			03/28/01
OC	A3	09/819,344		Okoroanyanwu et al.			03/28/01
OC	A4	09/819,552		Gabriel et al.			03/28/01
OC	A5	09/819,692		Okoroanyanwu et al.			03/28/01
OC	A6	09/820,143		Okoroanyanwu et al.			03/28/01
OC	A7	6,107,172	08/22/00	Yang et al.	438	585	
OC	A8	6,103,457	08/15/00	Gabriel	430	318	
OC	A9	5,965,461	10/12/99	Yang et al.	438	717	
OC	A10	5,003,178	03/26/91	Livesay	250	492.300	

FOREIGN PATENT DOCUMENTS

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION YES NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

OC	A11	Livesay, W. R., "Large-area electron-beam source," Journal of Vacuum Science & Technology B, Vol. 11, No. 6, Nov./Dec. 1993, pp. 2304-2308, American Vacuum Society
OC	A12	Yank, J. J. et al., "Electron Beam Processing for Spin-on Polymers and its Applications to Back-End-of-Line (BEOL) Integration," Materials Research Society Symposium Proceedings, Vol. 511, 1998, pp. 49-55, Materials Research Society
OC	A13	Ross et al., "Plasma Etch Characteristics of Electron Beam Processed Photoresist," The Society of Photo-Optical Instrumentation Engineers, Vol. 2438, 1995, pp. 803-816, SPIE- The International Society for Optical Engineering
OC	A14	Grün, Von A.E., "Lumineszenz-photometrische Messungen der Energieabsorption im Strahlungsfeld von Elektronenquellen Eindimensionaler Fall in Luft," Zeitschrift für Naturforschung, Vol. 12a, 1957, pp. 89-95. Publisher: Zeitschrift für Naturforschung; full English Translation attached (11 pgs.)

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include any copy of this form with next communication to applicant.